

ABSTRACT

Determining the presence of a corrosion inhibitor on exposed surfaces during manufacture of a microelectronic device subjected to one or more cleaning operations using a cleaning solution containing a corrosion inhibitor where a
5 subsequent manufacturing or handling step requires no corrosion inhibitor residue on the device. A sacrificial copper test piece or coupon is subjected to the cleaning operation along with the device is exposed to hydrogen sulfide gas. The degree of color change in the surface of the copper test piece is a qualitative means of indicating the presence or absence of a corrosion inhibitor residue on exposed copper
10 surfaces of the microelectronic device.